



13: 1                    14:  
 15: 2                    16:  
 17: 3                    18: -  
 19:                    100:  
 100S:

(under cut)

(bridge)

(stack gate)

(fence)가

(residue)가

가

가

가

2 ; 1 ; 2 ; 2 ; 1 ; 2 ; 1 ; 2 ; 3 ; 2 ; 1 ; 2 ; 2 ; 1 ; 2 ; 10 ~ 50 % ; 2 ; 20 ~ 70 ; 100 ~ 250 %

2 1 2

가 , 가

1 2 8  
1 Y1-Y1 a 1 X-X b  
c 1 Y2-Y2

1, 2a, 2b 2c , (SA-STI) (11)  
(14) , (14) (12) 1  
(13) 1 (13) (14) 가  
2 (15)  
3 2 (15) (16) (16)  
(17) - (18) - (18) (19)  
(19) (strip)

1, 3a, 3b 3c , (19) - (18)  
(main etch) (over etch) 3 (17)  
1 3 (17)  
3 (17) 2 (15) (16) 3 (17)

1, 4a, 4b 4c , (19)  
3 (17) 2 1 3 (17) (etch damage)  
17) 1 (17) 3 10 ~ 50 %  
3 (17) 2 (15)

1, 5a, 5b 5c , 3 (17) 2  
(100)  
(100) 3 (17)  
(LPCVD) 100  
, 20 ~ 70

1, 6a, 6b 6c , (100) 3  
(17 18) (100S)  
(100) 100 ~ 250 % (10)  
0) (16) ONO(upper oxide/middle nitride/lower oxide)  
(16)

1, 7a, 7b 7c , (100S)가 (19)  
2 3 (17)  
2 3 (17)  
(100S)가 (16) 3 (17)  
3 (17)

1, 8a, 8b 8c , (19) 3  
(16), 2 (15) 1 (13) 1 2 (15)  
가

(18) 가 가 1 2 (13 15) 가 3 (17) 가 -

(57)

1.

1 ;

1 2 ;

2 ;

1 2 ;

2 ;

2 2 ;

3 1

2.

1 ,

1 1 2

3.

2 ,

1

4.

1 ,

2 -

5.

1 ,

1 2

, 2 10 ~ 50 %

6.

1 ,

20 ~ 70 ,

7.

6 ,

100 ~ 250 %

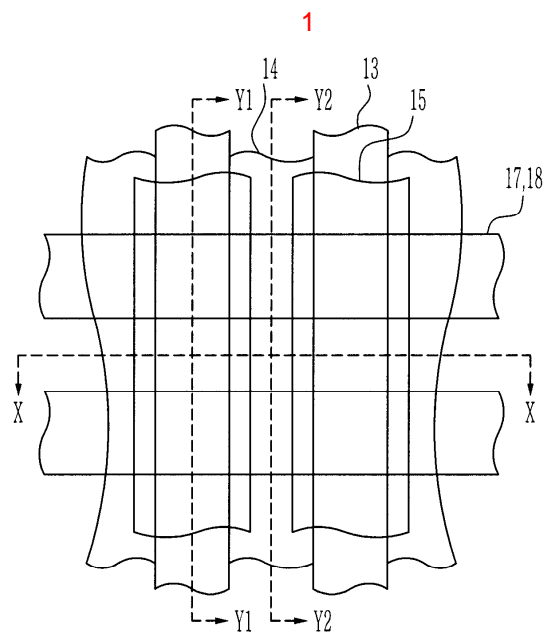
8.

1 ,

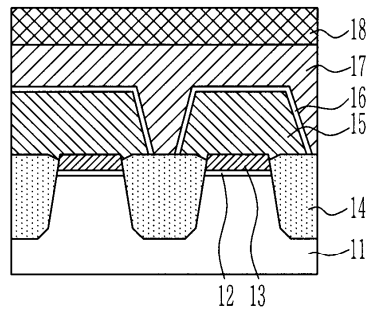
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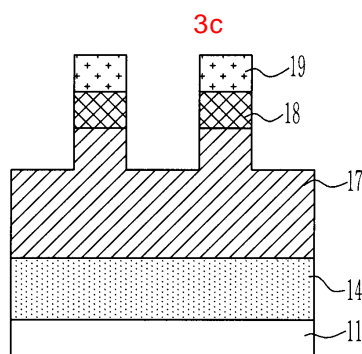
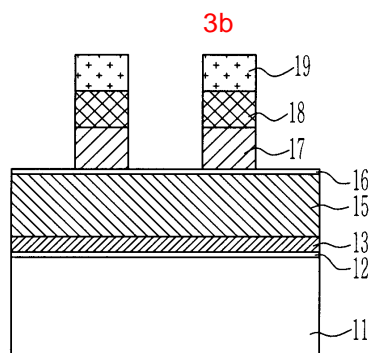
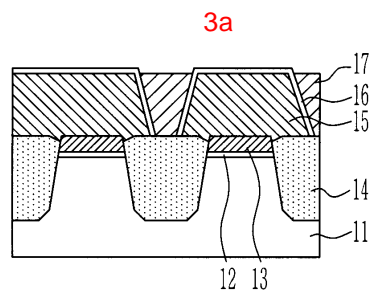
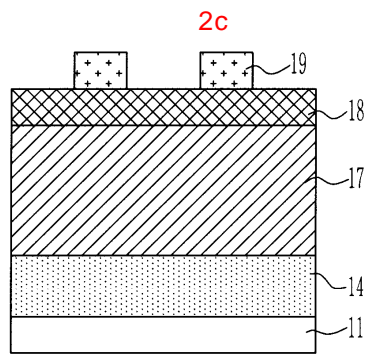
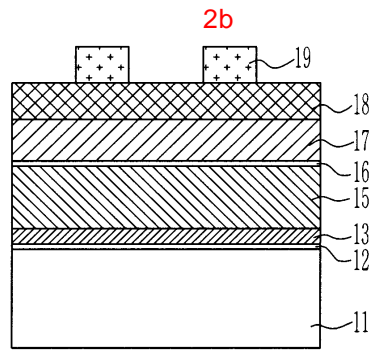
1

2

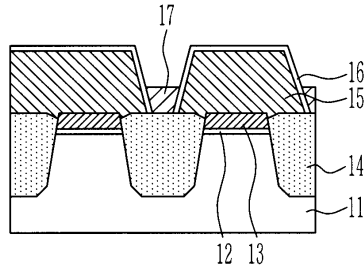


**2a**

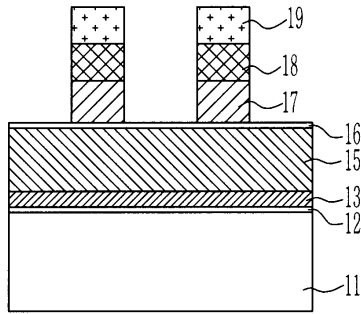




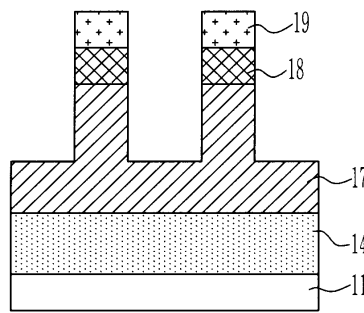
4a



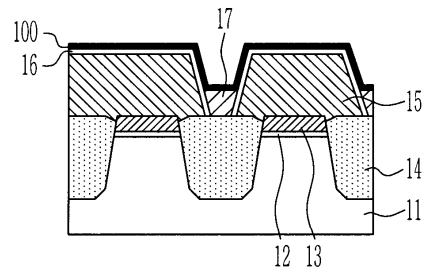
4b



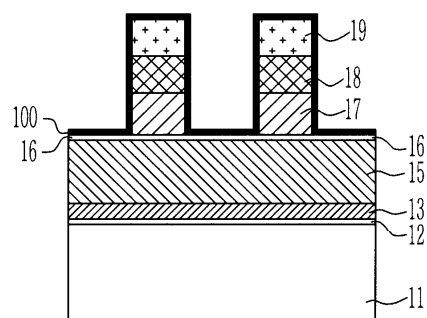
4c



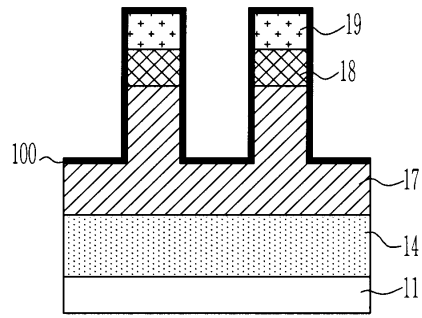
5a



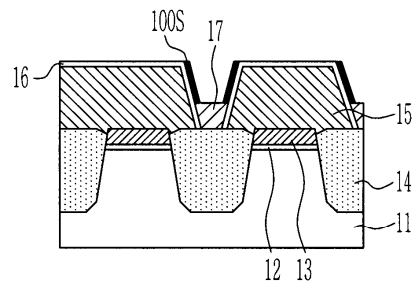
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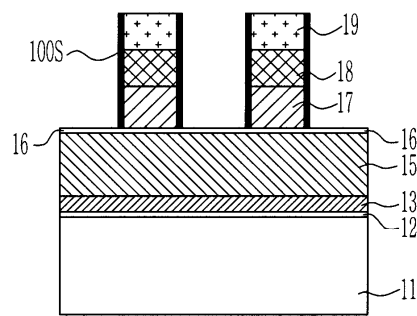
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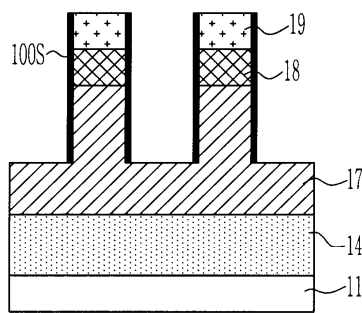
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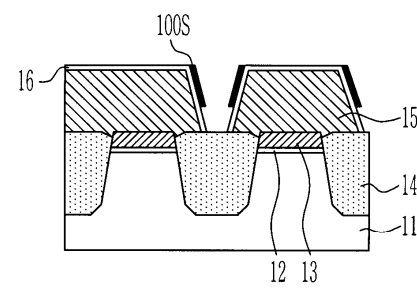
6b



6c

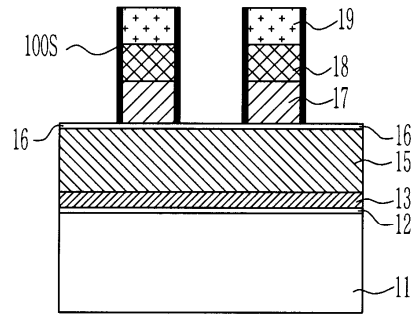


7a

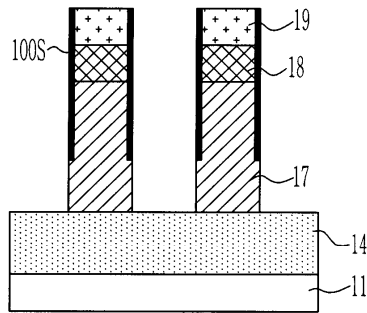




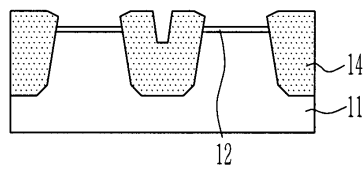
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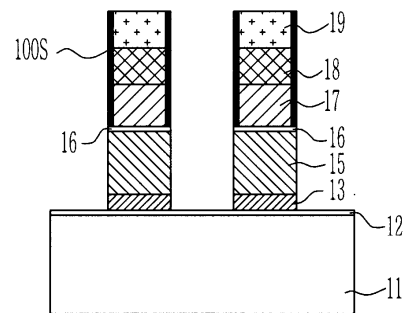
7c



8a



8b



8c

